

007034 USA P02/DSM/ELK/JW
Application No: 10/783,748
Page 2 of 9

IN THE CLAIMS

Please substitute the following listing of claims for the previous listing of claims:

1. (currently amended) A method for of cleaning a chamber of an electron beam treatment apparatus, the method comprising that comprises:
generating an electron beam that energizes a cleaning gas in a the chamber of the electron beam treatment apparatus;
monitoring an electron beam current;
adjusting a pressure of the cleaning gas to maintain the electron beam current at a substantially constant value; and
stopping when the cleaning gas pressure becomes substantially constant for a predetermined length of time a predetermined condition has been reached.
- 2-3. (cancelled).
4. (original) The method of claim 1 wherein the cleaning gas comprises an oxygen-based gas.
5. (original) The method of claim 4 wherein the oxygen-based gas comprises one or more of O₂, ozone, NO, and H₂O.
6. (original) The method of claim 1 wherein the cleaning gas comprises a fluorine-based gas.
7. (original) The method of claim 6 wherein the fluorine-based gas comprises one or more of NF₃, F₂, CF₄, C₂F₆, C₃F₈, SF₆.

007034 USA P02/DSM/ELK/JW
Application No: 10/7R3,748
Page 3 of 9

8. (Currently amended) A method ~~for~~ of cleaning an electron beam treatment chamber, the method comprising that comprises:

generating an electron beam that energizes a cleaning gas in ~~a~~ the electron beam treatment chamber of ~~the~~ the electron beam treatment apparatus; and
stopping after the cleaning gas pressure becomes substantially constant
for a predetermined length of time ~~a predetermined length of time has elapsed.~~

9. (original) The method of claim 8 wherein the cleaning gas comprises an oxygen-based gas.

10. (original) The method of claim 9 wherein the oxygen-based gas comprises one or more of O₂, ozone, NO, and H₂O.

11. (original) The method of claim 8 wherein the cleaning gas comprises a fluorine-based gas.

12. (original) The method of claim 11 wherein the fluorine-based gas comprises one or more of NF₃, F₂, CF₄, C₂F₆, C₃F₈, SF₆.

13. The method of claim 8 wherein a gas pressure of about 1 Torr or greater is maintained in the chamber.

14. (original) The method of claim 9 wherein a gas pressure of about 1 Torr or greater is maintained in the chamber.

15. (original) The method of claim 11 wherein a gas pressure of about 1 Torr or greater is maintained in the chamber.

007034 USA P02/DSM/ELK/JW
Application No: 10/783,740
Page 4 of 9

16. (new) A method of cleaning a chamber of an electron beam treatment apparatus, the method comprising:

Introducing a cleaning gas into the chamber;
generating an electron beam that energizes the cleaning gas in the chamber;
setting in the chamber, an electron beam current of about 10 mA or above;
adjusting a pressure of the cleaning gas to maintain the electron beam current at a substantially constant value; and
determining an endpoint of the cleaning process and stopping introduction of the cleaning gas when the cleaning gas pressure reaches a substantially constant value.

17. (new) The method of claim 16 wherein the cleaning gas comprises an oxygen-based gas.

18. (new) The method of claim 17 wherein the oxygen-based gas comprises one or more of O₂, ozone, NO, and H₂O.

19. (new) The method of claim 16 wherein the cleaning gas comprises a fluorine-based gas.

20. (new) The method of claim 19 wherein the fluorine-based gas comprises one or more of NF₃, F₂, CF₄, C₂F₆, C₃F₈, SF₆.